PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q93721

Hans-Juergen ROSTALSKI, et al.

Appln. No.: 10/571,267

Group Art Unit: Not Yet Assigned

Confirmation No.: Not Yet Assigned

Examiner: Not Yet Assigned

Filed: March 9, 2006

For:

LITHOGRAPHY LENS SYSTEM AND PROJECTION EXPOSURE SYSTEM PROVIDED WITH AT LEAST ONE LITHOGRAPHY LENS SYSTEM OF THIS TYPE

PRELIMINARY AMENDMENT

MAIL STOP AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the accompanying pages.

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